

first and second movable stages disposed in a certain movement plane so as to be movable independently of each other, the first movable stage holding a first substrate and the second movable stage holding a second substrate;

a scanning system which scans one of the first and second movable stages and the reticle stage along a scanning axis;

a first measurement system which measures within a first measurement range a position of one of the first and second movable stages, the first measurement system being capable of emitting a measurement beam to a mirror of each of the first and second movable stages;

a second measurement system which measures positions of the first and second movable stages within a second measurement range partially overlapping the first measurement range; and

a control system which corrects measurement results of the first and second measurement systems on the basis of the measurement results of the first and second measurement systems.--

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Song
--36. (New) The scanning exposure apparatus according to claim 35, wherein the first measurement system emits biaxial beams spaced apart in a direction perpendicular to the certain movement plane.--

--37. (New) The scanning exposure apparatus according to claim 36, wherein the second measurement system emits biaxial beams spaced apart in a direction perpendicular to the certain movement plane.--

--38. (New) The scanning exposure apparatus according to claim 35, wherein the second measurement system emits biaxial beams spaced apart in a direction perpendicular to the certain movement plane.--

--39. (New) The scanning exposure apparatus according to claim 35, wherein the first measurement system emits the measurement beam along the scanning axis.--